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	Application No.	Applicant(s)	
Notice of Allowability	10/601,239	OH ET AL.	
	Examiner	Art Unit	
	Anthony J. Canning	2879	
The MAILING DATE of this communication apperall claims being allowable, PROSECUTION ON THE MERITS IS therewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI	(OR REMAINS) CLOSED in or other appropriate commul GHTS. This application is su	this application. If not included nication will be mailed in due c	d course. THIS
1. \square This communication is responsive to <u>6/20/03</u> .			
2. 🔀 The allowed claim(s) is/are <u>1-6</u> .			
3. The drawings filed on 20 June 2003 are accepted by the Ex	xaminer.		
 4. Acknowledgment is made of a claim for foreign priority una) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" on noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give 6. CORRECTED DRAWINGS (as "replacement sheets") mus (a) including changes required by the Notice of Draftspers 1) hereto or 2) to Paper No./Mail Date 	been received. been received in Application cuments have been received of this communication to file ENT of this application. tted. Note the attached EXA is reason(s) why the oath or the submitted.	in this national stage application in this national stage application is deficient.	uirements
(b) ☐ including changes required by the attached Examiner's	Amendment / Comment or	in the Office action of	
Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the	84(c)) should be written on the ne header according to 37 CFF	e drawings in the front (not the	back) of
 DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT I 			ote the .
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☑ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. 🗌 Interview Su	ormal Patent Application (PTO mmary (PTO-413), Mail Date	-152)
 Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 6/20/2003 	8), 7. Examiner's A	Amendment/Comment	٠.
 Examiner's Comment Regarding Requirement for Deposit of Biological Material 	8.	Statement of Reasons for Allov	vance
C. Diological material	· · ·	•	

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DETAILED ACTION

Allowable Subject Matter

Claims 1-6 are allowed over the prior art of record.

The following is an examiner's statement of reasons for allowance:

Regarding claim 1, the references of the Prior Art of record fails to teach or suggest the combination of the limitations as set forth in claim 1, and specifically comprising the limitation of the front surface of the shadow mask's aperture area satisfying the conditions of 100%<RMV'/RMV<110% and 12%RMS/RMV'<150%, where RMV is a vertical radius of curvature of the front surface of the aperture area with respect to a vertical direction passing through a center of the aperture area, RMS is a vertical radius of curvature of the front surface of the aperture area with respect to a short side of the aperture area, and RMV' is a vertical radius of curvature of the front surface of the aperture area with respect to the vertical direction at a location on a horizontal axis passing through the center of the aperture area.

Regarding claims 2 and 3, claims 2 and 3 are allowable for the reasons given in claim 1 because their dependency status from claim 1.

Regarding claim 4, the references of the Prior Art of record fails to teach or suggest the combination of the limitations as set forth in claim 4, and specifically comprising the limitation of the front surface of the shadow mask's aperture area satisfying the conditions of 100%<RMV'/RMV<110% and 12%RMS/RMV'<150%, where

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RMV is a vertical radius of curvature of the front surface of the aperture area with respect to a vertical direction passing through a center of the aperture area, RMS is a vertical radius of curvature of the front surface of the aperture area with respect to a short side of the aperture area, and RMV' is a vertical radius of curvature of the front surface of the aperture area with respect to the vertical direction at a location on a horizontal axis passing through the center of the aperture area.

Regarding claims 5 and 6, claims 5 and 6 are allowable for the reasons given in claim 11 because their dependency status from claim 4.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Prior Art

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Hirai et al. (U.S. 5,606,217) discloses a shadow mask with radii of curvature and three-dimensional spatial relations of said radii of curvature.

Nose et al. (U.S. 2001/0011864 A1) discloses a shadow mask wherein the radius of curvature for the major and minor sides of the mask are given.

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Contact Information

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Anthony J. Canning whose telephone number is (571)-272-2486. The examiner can normally be reached on M-F 8:00-4:30.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nimesh D. Patel can be reached on (571)-272-2457. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Anthony Canning M

1 February 2005

ASHOK PATEL
PRIMARY EXAMINER

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